

Please add the following claim:

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-- 45. The target body according to Claim 44, wherein the magnetron source comprises a magnetic circuit arrangement operable to generate a magnetic field over the atomization surface, including an anode arrangement, a receiving frame which extends around an edge of the target body and is electrically insulated with respect thereto, which receiving frame has a receiving opening for at least one workpiece to be coated, and the atomization surface and a surrounding non-atomized residual interior surface of the receiving frame being sized and arranged relative to one another such that a process space bounded substantially by the atomization surface of the target body and the surrounding non-atomized residual interior surface, F_9 , of the receiving frame, except for the receiving opening for the at least one workpiece, satisfies the relationship $\leq 50\% F_1$, to minimize the surrounding non-atomized residual interior surface thereby to ensure, during an atomizing operation, a stable plasma discharge.--

REMARKS

The requirement of a supplemental oath, the objection to the specification under 35 U.S.C. §132 and the rejection of Claims 35-37 and 44 under 35 U.S.C. §112, first paragraph, are traversed, and reconsideration is requested. Applicants would note that the objections to the Declaration, and to the specification and the rejection of the claims are all based upon